

**Amendments to the Claims:**

Claims 1 and 9 been amended herein. New claims 16 - 19 are added. Please note that all claims currently pending and under consideration in the referenced application are shown below. This listing of claims will replace all prior versions and listings of claims in the application.

**Listing of Claims:**

1. (Currently amended) An etchant solution which selectively etches borophosphosilicate glass over tetraethyl orthosilicate, the etchant solution consisting essentially of an organic acid and a fluoride-containing solution provided in a selected volumetric ratio relative to one another, wherein the selected volumetric ratio of the organic acid to the fluoride-containing solution is about 10:1 to about 500:1.
2. (Previously presented) The etchant of claim 1, wherein the organic acid is selected from the group consisting of acetic acid, formic acid, and oxalic acid.
3. (Previously presented) The etchant of claim 1, wherein the fluoride-containing solution is selected from the group consisting of hydrofluoric acid and ammonium fluoride.
4. (Previously presented) The etchant of claim 1, wherein the organic acid comprises glacial acetic acid and the fluoride-containing solution comprises 49% hydrofluoric acid by weight in water.
5. (Canceled)
6. (Previously presented) The etchant of claim 4, wherein the acetic acid is in a volumetric ratio with the hydrofluoric acid at about 10:1 to about 100:1.

7. (Previously presented) The etchant of claim 1, wherein the organic acid comprises glacial acetic acid and the fluoride-containing solution comprises 40% ammonium fluoride by weight in water.
8. (Previously presented) The etchant of claim 1, wherein the etchant solution exhibits a selectivity ratio of borophosphosilicate glass to tetraethyl orthosilicate between about 27:1 and 55:1.
9. (Currently amended) An etchant solution which selectively etches borophosphosilicate glass over tetraethyl orthosilicate, the etchant solution consisting ~~essentially~~ of an organic acid selected from the group consisting of acetic acid, formic acid, and oxalic acid and a fluoride-containing solution, wherein the etchant solution exhibits a selectivity ratio of borophosphosilicate glass to tetraethyl orthosilicate between about 27:1 and 55:1.
10. (Canceled)
11. (Original) The etchant of claim 9, wherein the fluoride-containing solution is selected from the group consisting of hydrofluoric acid and ammonium fluoride.
12. (Original) The etchant of claim 9, wherein the organic acid comprises glacial acetic acid and the fluoride-containing solution comprises 49% hydrofluoric acid by weight in water.
13. (Original) The etchant of claim 12, wherein the acetic acid is in a volumetric ratio with the hydrofluoric acid at about 1:1 to about 500:1.
14. (Original) The etchant of claim 12, wherein the acetic acid is in a volumetric ratio with the hydrofluoric acid at about 10:1 to about 100:1.

15. (Original) The etchant of claim 9, wherein the organic acid comprises glacial acetic acid and the fluoride-containing solution comprises 40% ammonium fluoride by weight in water.
16. (New) The etchant of claim 1, wherein the organic acid is oxalic acid.
17. (New) The etchant of claim 9, wherein the organic acid is oxalic acid.
18. (New) An etchant solution which selectively etches borophosphosilicate glass over tetraethyl orthosilicate, the etchant solution consisting of oxalic acid and a fluoride-containing solution.
19. (New) The etchant of claim 18, wherein the fluoride-containing solution is selected from the group consisting of hydrofluoric acid and ammonium fluoride.